

Resource Summary Report

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Oxford: PlasmaPro 100 PECVD Plasma Technology

RRID:SCR_020374

Type: Tool

Proper Citation

Oxford: PlasmaPro 100 PECVD Plasma Technology (RRID:SCR_020374)

Resource Information

URL: <https://plasma.oxinst.com/products/pecvd/plasmapro-100-pecvd>

Proper Citation: Oxford: PlasmaPro 100 PECVD Plasma Technology (RRID:SCR_020374)

Description: PECVD process modules are designed to produce uniformity and high rate films, with control of film properties such as refractive index, stress, electrical characteristics and wet chemical etch rate.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 100 PECVD Plasma Technology

Resource ID: SCR_020374

Alternate IDs: Model_Number_100_PECVD

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260919T195434+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 PECVD Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 PECVD Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.